Magnetron Sputter System

Model: SA-VKM800

SA-VKM800 is a high-precision magnetron sputter system. It delivers superior coating uniformity and features low-maintenance design, fulfilling both mass-production and laboratory requirements for high-precision reactive magnetron sputtering and hole-filling processes.

Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

Application

- Laser
- R&D
- Intergated circuit
- MEMS

Specifications：

Parameter	Descriptions
Number of Cathodes	4(max.)
Sputtering Power Supply	DC / RF / pulsed DC, freely switchable
Ion Source	RF & Kaufman & Hall ion source
Bias	RF / pulsed DC
Vacuum Sampling Chamber	Multi-wafer fully-automatic sampling chamber, optional
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Flow Control	Digital mass flow meter
Coating Uniformity	±1.5%
Coating Repeatability	±2%
Uniform Deposition Area	5×Ø300 mm(max.)
Ultimate Vacuum	1E-5Pa
Vacuum Measurement	Full-range vacuum gauge + Capacitance diaphragm gauge
Temperature Control Range	-50~800℃
Space Requirements(L×W×H,m)	3.2×3.3×2.2

Principle：